VALQUA Semiconductor Industry Products

HYREC ARMOR ™

High Performance FKM

Product & Benefits

HYREC ARMOR™ is a softer FKM suited for static seal locations, with excellent purity and improved radical resistance compared to the conventional FKM. It may be used for dry etch, ashing, CVD processes.



- A Softer FKM with Excellent Compression Set for Static Locations
- Low Adhesion to Metal and Improved Radical Resistance

Applications

- Dry Etch Equipment
- Plasma Enhanced CVD Equipment
- Plasma Ashing Equipment

Contact Us

Valqua America, Inc. 4655 Old Ironsides Dr #380 Santa Clara, CA 95054 www.valqua-america.com



Typical Properties

Transparent
Deep Amber
58
13.0
440
1.2
200
38

Compression Set: 25% compression at 200℃ for 72 hours Values above are actual measurements, not standards

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Valqua America, Inc.

+1-408-986-1425 Tel:

Email: info@valqua-america.com

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Performance Properties

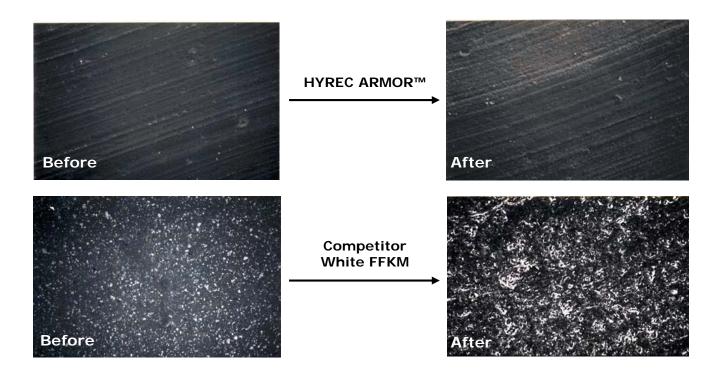
Actual Equipment Evaluation Example

Scanning electron micrograph of elastomer surface after plasma exposure

Equipment: Etcher

O-ring Size: AS568A-207 **Gas**: Cl₂ +BCl₃+Ar **Plasma Power**: 1000-1500W **Temp**: 100-200°C

Evaluation Period: HYREC ARMOR 2 months Competitor 1.5 months





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